

152/1765-

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Ryoji HOSHI et al.

Attn: OIPE

Application No.: 10/520,099

Docket No.: 122336

Filed: January 4, 2005

For: A SILICON WAFER FOR EPITAXIAL GROWTH, AN EPITAXIAL WAFER, AND
A METHOD FOR PRODUCING IT

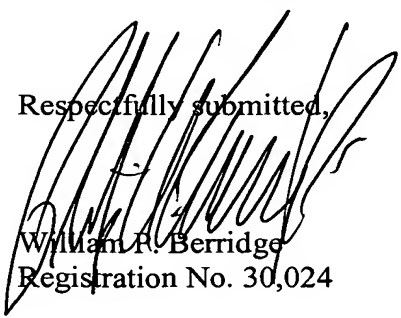
REQUEST FOR CORRECTION OF PALM RECORDS

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Attached is a photocopy of the original filing receipt on which errors have been corrected in red. These errors are being brought to the attention of the Patent and Trademark Office so that it may correct its records in accordance with the Preliminary Amendment filed concurrently herewith.

Respectfully submitted,



William R. Berridge
Registration No. 30,024

Philip A. Caramanica, Jr.
Registration No. 51,528

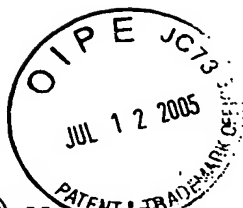
WPB:PAC/nxy

Date: July 12, 2005

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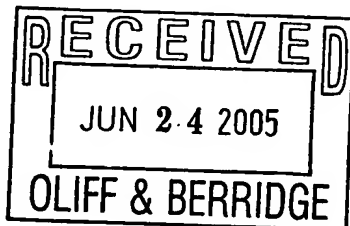
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/520,099	01/04/2005	1765	1350	122336	6	29	3

CONFIRMATION NO. 9147

25944
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FILING RECEIPT



OC000000016320304

Date Mailed: 06/22/2005

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Applicant(s)

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Assignment For Published Patent Application

Shin-Etsu Handotai Co., Ltd., Tokyo, JAPAN

Power of Attorney: The patent practitioners associated with Customer Number 25944.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP03/08671 07/08/2003

Foreign Applications

JAPAN 2002-204703 07/12/2002

Projected Publication Date: 09/29/2005

*** PLEASE SEE PAGE 2 FOR CORRECTIONS TO THE TITLE ! ***

Non-Publication Request: No

Early Publication Request: No

Title

~~Silicon wafer for epitaxial growth, epitaxial wafer, and its manufacturing method~~

~~A SILICON WAFER FOR EPTAXIAL GROWTH, AN EPTAXIAL WAFER, AND A METHOD FOR PRODUCING IT~~

Preliminary Class

117

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